

SPUTTERING TARGET

ABSTRACT

5 A sintered compact sputtering target having a structure in which metal phases
and oxide phases are uniformly dispersed, wherein the metal phases contain Co, Pt
and Mn as components, and the oxide phases contain an oxide having at least Mn
as a constituent. The sputtering target of the present invention yields superior
10 effects of being able to reduce the amount of particles generated during sputtering
and improve the yield during deposition.

Fig.1